

Materials List for:

# Flow-assisted Dielectrophoresis: A Low Cost Method for the Fabrication of High Performance Solution-processable Nanowire Devices

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URL: <https://www.jove.com/video/56408>

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## Materials

Name	Company	Catalog Number	Comments
Silicon/silicon dioxide wafer, CZ method growth, 100mm diameter, 300 nm oxide thermal growth, n-doped phosphorus	Si-Mat (Silicon materials)	-	<a href="http://si-mat.com/">http://si-mat.com/</a>
Acetone (200ml)	Sigma Aldrich	W332615	-
Isopropanol (200ml)	Sigma Aldrich	W292907	-
Deionised water (150ml)	On site supply	-	-
Photoresist (A) SF6 PMGI under etch photoresit (approx 1 ml per sample)	Microchem	-	<a href="http://microchem.com/pdf/PMGI-Resists-data-sheetV-rhcedit-102206.pdf">http://microchem.com/pdf/PMGI-Resists-data-sheetV-rhcedit-102206.pdf</a>
Photoresist (B) S1805 photoresit (approx 1 ml per sample)	Microchem	-	<a href="http://www.microchem.com/PDFs_Dow/S1800.pdf">http://www.microchem.com/PDFs_Dow/S1800.pdf</a>
Photoresist developer Microposit MF319 (100ml)	Microchem	-	<a href="http://microchem.com/products/images/uploads/MF_319_Data_Sheet.pdf">http://microchem.com/products/images/uploads/MF_319_Data_Sheet.pdf</a>
Photoresist remover Microposit remover 1165 (300ml (2 baths 150 each))	Microchem	-	<a href="http://micromaterialstech.com/wp-content/dow_electronic_materials/datasheets/1165_Remover.pdf">http://micromaterialstech.com/wp-content/dow_electronic_materials/datasheets/1165_Remover.pdf</a>